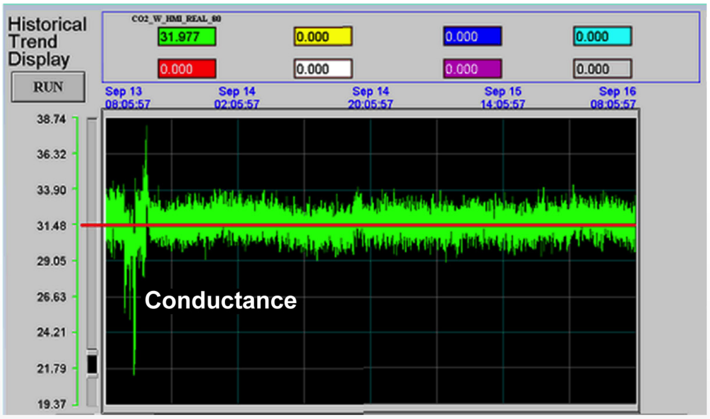
Trusval CO_2 DI Water Delivery System

Trusval Product Spec Sheet

The Trusval Technology CO_2 DI Water Delivery System is used for wet cleaning applications and provides high purity DI water that is also conductive, eliminating ESD risk in wet cleaning and grinding applications, where SOI and other devices might otherwise be prone to damage.

Much more efficient than membrane-based technology or CO_2 bubbling, a single Trusval CO_2-DIW system can deliver up to 80 liters per minute of conductive CO_2 charged water for use in critical wet process steps where the stability of the water conductivity is critical. For certain process steps the CO_2-charged water has proven to be an effective replacement for NMP, while also delivering improved process performance.

The system relies on a CO_2 concentration technology that is 100% efficient in the use of CO_2 and DI water inputs, delivering exceptionally consistent water at a high volumes.



The Trusval CO_2-DIW system delivers exceptionally consistent and stable CO_2-saturated DI water at high volume. After initial setup and adjustment, the graph shows the delivery of process $C0_2$-DI water at 31.5 microsiemens of measured conductance with a range of 2 microsiemens at a flow rate of 50 liters per minute.

Equipment Advantages

- Maintain CO_2-DIW conductivity stability at high volumes
- Minimizes CO_2 consumption - no bleeding, capture and re-dissolve of gas-out required
- Maintains stable conductivity when system is idle

Utility Matrix:	
Conductivity	33 +/- 2 uS/cm (adjustable: 10-90 uS/cm or 0.01-0.1 M-ohm/cm)
Throughput	Avg: 4-80 LPM (under 33 uS/cm)
DIW	2”, Pressure: 60 Psig, Flow Rate: >80 LPM 1”, Pressure: 40-60 Psig, Flow Rate: >30 LPM
CO_2	3/8” x 1, Pressure: 60 Psig, Flow Rate: > 30 LPM
CO_2 Consumables	0.407 g/L (33 uS/cm CO2-DIW)
N_2	1/2” x 1, Pressure: >80 Psig, Flow Rate: >30 LPM
CDA	3/8” x 1, Pressure: >80 Psig, Flow Rate: >30 LPM
Drain	1” x 1
Power	220V, 3-Phase, 4 wire, 60Hz, 15A
Exhaust	4” x 1

DIMENSIONS		
Metric (mm)	1118W x 1194D x 1854H	
Inches	44W x 47D x 73H	
Weight	630 kg	1400 lbs

About Axus Technology

Axus Technology is the industry expert in providing material processing and CMP foundry and wafer grinding services, process tools, and custom configured upgrades that are designed to meet your process and production requirements. We deliver leading-edge CMP, wafer thinning and wafer polishing solutions for semiconductor, MEMS and substrate applications.

Customer support services include tool upgrades, spare parts, and field service support for a range of CMP and wafer grinding tools, including installed legacy tools.

About Trusval

Trusval Technology, headquartered in Hsinchu, Taiwan, is a leading supplier of chemical management and dispense products in Asia with an expanding global presence. With a staff of more than 300, Trusval delivers specialized chemical delivery and management systems, as well as providing facility and system integration support.

Performance Guarantee

Axus Technology is committed to customer satisfaction. While we aggressively pursue the cost and performance goals of our clients, we never compromise on quality or technical performance.

Contact Axus Technology or your local Axus Technology Sales Representative to discuss how Axus can help you get the most from your equipment investment.